

LIST OF PUBLICATIONS CITED BY APPLICANT	<u>Attorney Docket No.</u>	<u>Serial No.</u>
	HAG 111	Not Assigned
	<u>Applicant</u>	U.S. PRO Tsutomu SHOKI
	<u>Filing Date</u> Herewith	<u>Group</u>

jc518 U.S. PRO
05/26/98
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U. S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
AR	5,005,075	04/02/91	Kobayashi et al	378	35	01/30/90
AR	5,178,977	01/12/93	Yamada et al	378	35	01/18/90

FOREIGN PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
AR	JP 7-75219	08/09/95	Fujitsu Ltd.			07/25/89

OTHER PUBLICATIONS (Including Author, Title, Date, Pertinent Pages)	
AR	1) English language abstract: Japanese Laid-Open Patent No. 7-75219. 8/95 2) Yamaguchi, Y.I. et al, "Properties of SiC Film as X-Ray Mask Membrane," Materials Research Laboratory, Hoya Corporation, pp. 197-210. 1993

EXAMINER <u>J. Dorasco</u>	DATE CONSIDERED <u>3/99</u>
*EXAMINER: Initial if reference considered, whether or not citation is in conformance and not considered. Include a copy of this form with the next communication to applicant.	